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Sequence Listing was accepted.

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Reviewer: Keisha Douglas

Timestamp: [year=2008; month=9; day=22; hr=12; min=30; sec=59; ms=945;]

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Application No: 10591827 Version No: 1.0

Input Set:

Output Set:

Started: 2008-08-22 17:42:58.631
Finished: 2008-08-22 17:42:59.716
Elapsed: 0 hr(s) 0 min(s) 1 sec(s) 85 ms
Total Warnings: 3
Total Errors: 0
No. of SeqIDs Defined: 3
Actual SeqID Count: 3

Error code	Error Description
W 213	Artificial or Unknown found in <213> in SEQ ID (1)
W 213	Artificial or Unknown found in <213> in SEQ ID (2)
W 213	Artificial or Unknown found in <213> in SEQ ID (3)

SEQUENCE LISTING

<110> KYOWA HAKKO KOGYO CO., LTD.
YAMAUCHI, Masahiro
KATO, Yasuki

<120> COMPLEX PARTICLES AND COATED COMPLEX PARTICLES

<130> 2006_1488A

<140> 10591827

<141> 2008-08-22

<150> JP 2004-067688

<151> 2004-03-10

<160> 3

<170> PatentIn version 3.4

<210> 1

<211> 20

<212> DNA

<213> Artificial

<220>

<223> Synthetic construct

<400> 1

actagtggct agcgaatctc

20

<210> 2

<211> 21

<212> RNA

<213> Artificial

<220>

<223> Synthetic construct

<220>

<221> misc_feature

<222> (20)..(21)

<223> n is dT

<400> 2

cuggaucgua agaaggcagn n

21

<210> 3

<211> 21

<212> RNA

<213> Artificial

<220>

<223> Synthetic construct

<220>

<221> misc_feature

<222> (20)..(21)

<223> n is dT

<400> 3

cugccuucuu acgauccagn n

21